

# The EII Cavities program at CERN: Atomic layer deposition

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# Contents

- *Atomic Layer deposition*
- *Secondary electron yield*
- *Multilayers*
- *Perspectives*

# Atomic Layer Deposition



Thin films ( $\leq 1 \mu\text{m}$ ) synthesis technique based on self-limiting surface chemical reactions. Sequential injection of vapor phase precursors . Layer by layer growth. Cycles.

## ➤ Advantages:

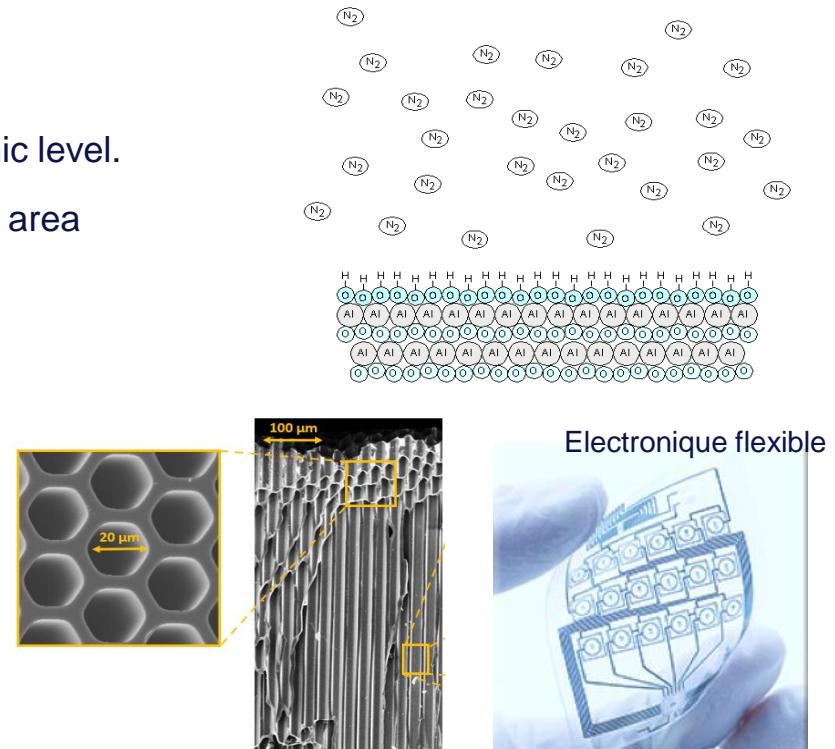
- Thickness and composition control down to the atomic level.
- Pin-hole free films.
- Excellent conformality on complex-shaped and large area substrates.
- Large palette of materials.
- Low temperatures (RT-450°C)

## ➤ Limits:

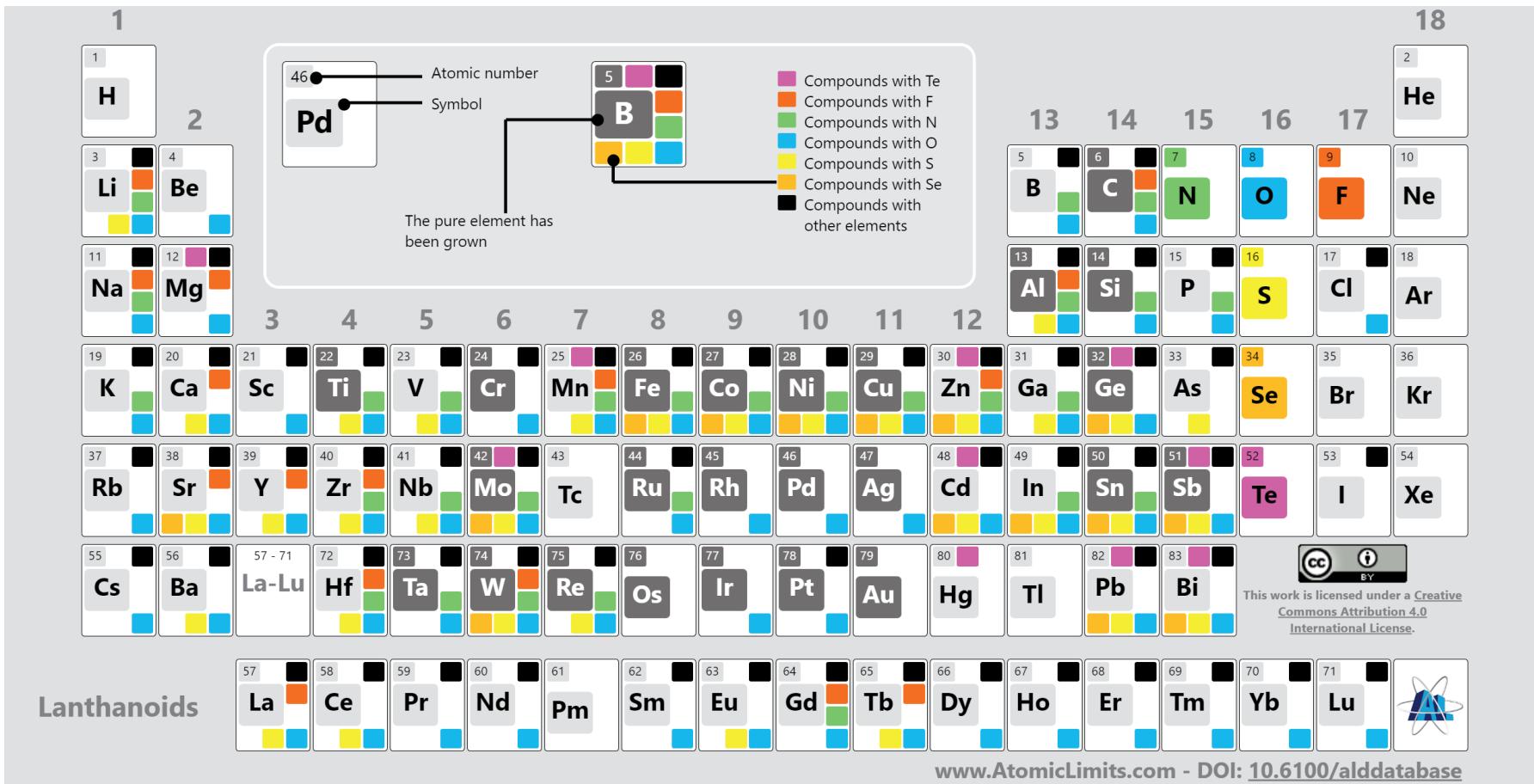
- Slow deposition (0.3 to 10 Å/min).
- New materials require new chemistry.

## ➤ Applications:

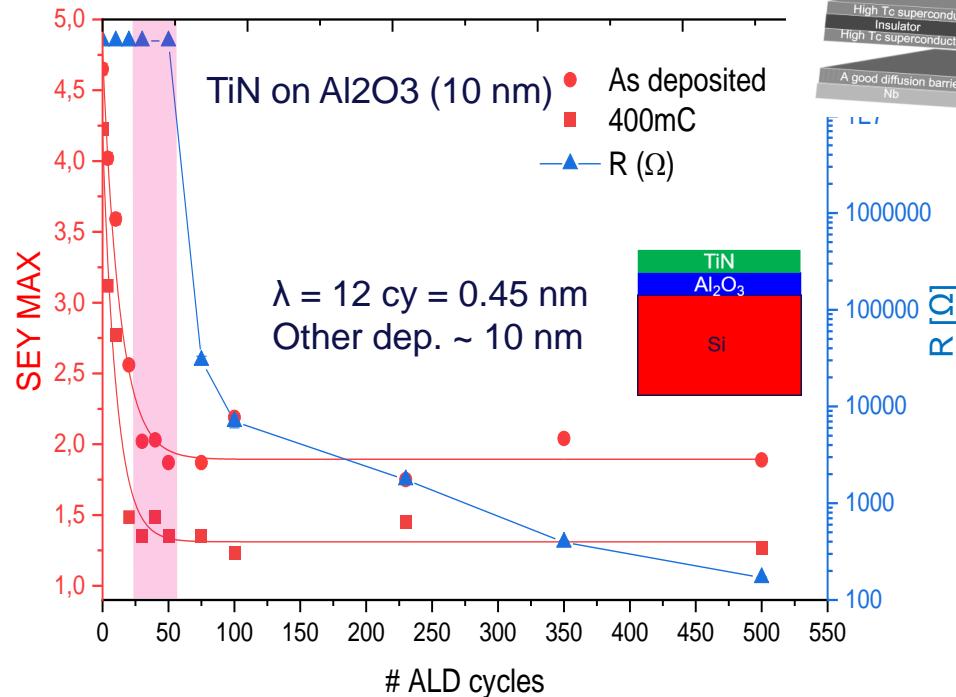
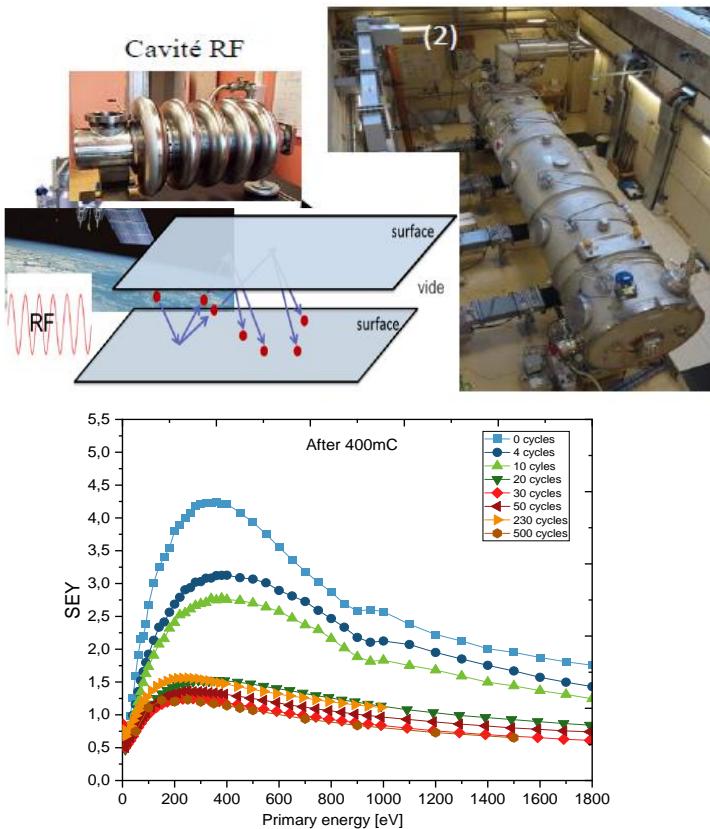
- Micro-electronic, Photovoltaic, Catalysis, Batteries, Detectors...



# Atomic Layer Deposition – Materials

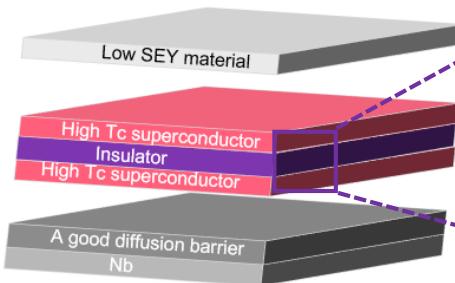


# Secondary electron yield – Mitigate Multipacting



- Control thickness and chemical composition – uniformity
- Tune SEY and electrical conductivity
- Wide variety of substrates (Nb, Cu...)

# Multilayers – increase SRF cavities performances (Q and E<sub>max</sub>)

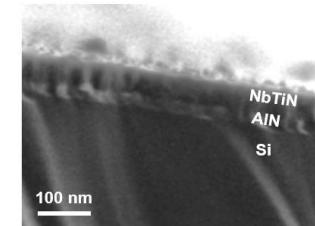


## Superconducting alloys – NbTiN/AlN

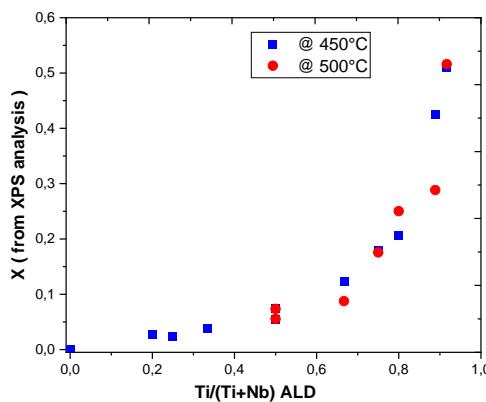
- Motivation: NbTiN has good superconducting performance ( $T_c = 17$  K)

- AlN as an insulating layer.

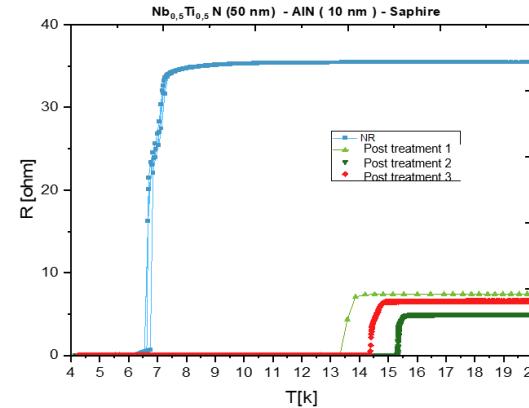
- Chemistry: Combination of TiN and NbN cycles:



- Tune chemical composition

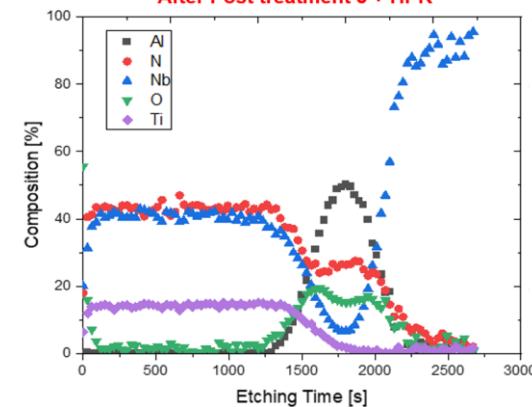


- Good superconducting properties



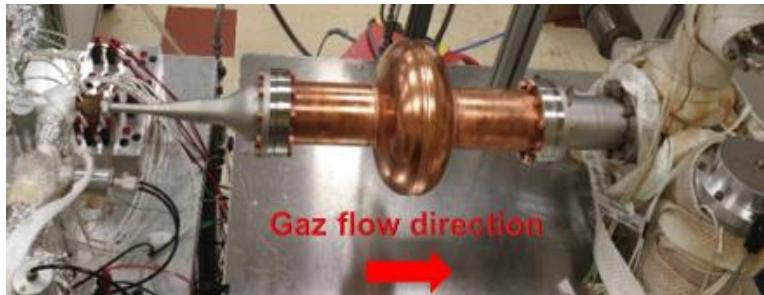
- Compatible with SRF cavities treatments

NbTiN (50 nm) - AlN (10 nm) - Nb  
After Post treatment 3 + HPR

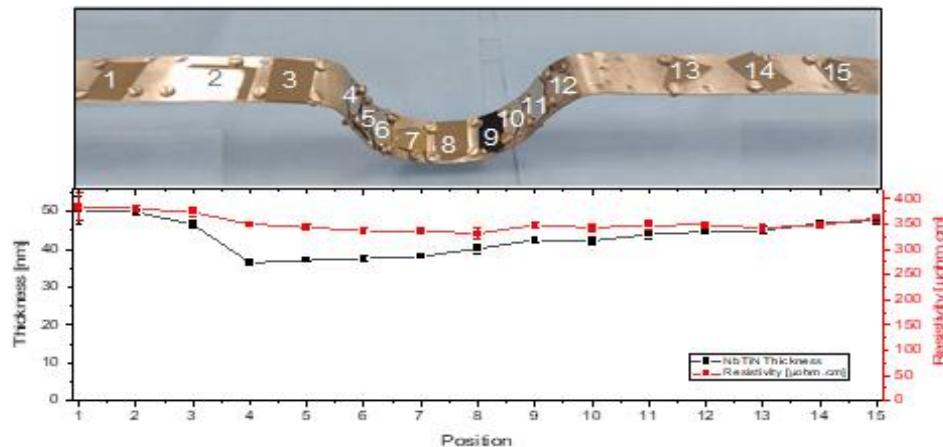


- All conditions are met to apply/test this theory on **SRF cavities**.

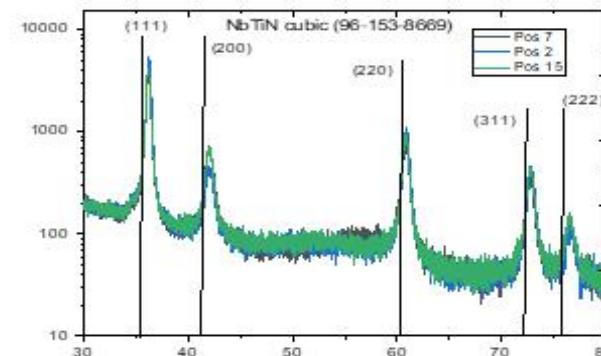
# From coupons to Cavities...



Test 2 : purge 20s



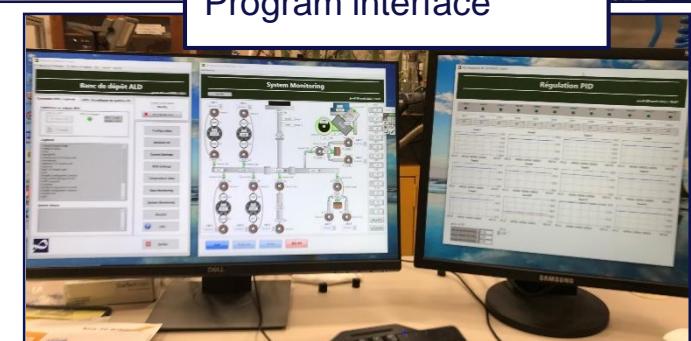
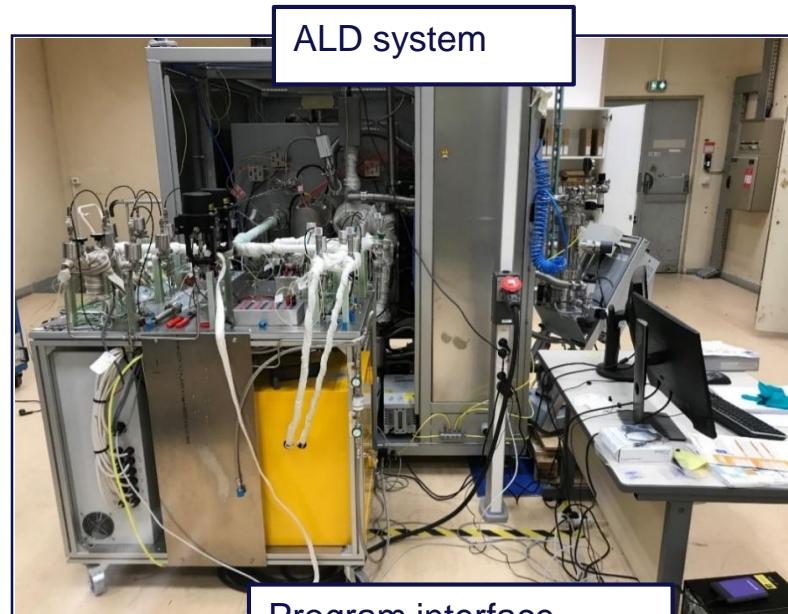
GIXRD diffraction patterns on different samples



- Optimized deposition parameters on RF cavities.
- Homogeneous deposition (thickness, Tc and structure) over 1,3 GHz Nb and Cu test cavity.

# Cavity dedicated ALD apparatus

- High vacuum oven:
  - 650°C – 10<sup>-6</sup> mbar / 900°C 1bar N<sub>2</sub>
  - Volume retort:  $\Phi = 49$  cm, L= 110 cm  
(Cavities sizes > 0.6 GHz)
- ALD system:
  - 9 precursor lines (2 gases, 2 liquids, 4 solids, 1 Ultra high temp.).
  - RGA synthesis monitoring.
- Interface and control:
  - Labview program of ALD system and Oven.
  - Automatic synthesis parameter control and monitoring.
- Status:
  - Deposition tests on samples
  - Future: Deposition on cavities



## Conclusion-Perspectives:

- ✓ SEY: ALD of TiN film is promising to reduce multipacting inside RF cavities.
- ✓ Growth of NbTiN and the multilayers AlN/NbTiN by ALD with good superconducting properties, homogeneous composition and thickness control over large surface areas (RF cavities).
- ✓ Control doping and surface engineering -> no post treatment chemistry.

### Future Goals :

- SEY: Test the  $\text{Al}_2\text{O}_3$ -TiN structure on Niobium RF cavities.
- Multilayer: Test the NbTiN-AlN structure on Niobium RF cavities.
- Doping: Test ALD doping procedure on SRF cavityies
- New directions:
  - ALD on Copper complementary to HIPIMS: insulating barrier - Nucleation and thermo-currents.
  - ALD for detectors/optics.

# Thank you for your attention

## Questions ?

## Acknowledgements

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